



10-15-04

Ifw

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No.10/664,744
Filing DateSeptember 18, 2003
InventorMichael T. Andreas
AssigneeMicron Technology, Inc.
Group Art Unit2823
ExaminerFernando L. Toledo
Attorney's Docket No.MI22-2711
Title Method of Polishing a Semiconductor Substrate, Post-CMP Cleaning
Process, and Method of Cleaning Residue from Registration Alignment
Markings (As Amended)

RESPONSE TO SEPTEMBER 23, 2004 OFFICE ACTION

To: Mail Stop Amendment
Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

VIA EXPRESS MAIL

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)
Wells St. John P.S.
601 West First Avenue, Suite 1300
Spokane, WA 99201-3828

Responsive to the Office Action dated September 23, 2004, Applicant
amends and remarks as follows:

AMENDMENTS

In the Title

Please replace the title with:

--Method of Polishing a Semiconductor Substrate, Post-CMP Cleaning Process, and Method of Cleaning Residue from Registration Alignment Markings--.